

Notice of References Cited

Application No.

09-859,655

Applicant(s)

Golecki

Examiner

George Goudreau

Group Art Unit

1763

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U.S. PATENT DOCUMENTS

*		DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS
	A					
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FOREIGN PATENT DOCUMENTS

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	N						
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	T						

NON-PATENT DOCUMENTS

*		DOCUMENT (Including Author, Title, Source, and Pertinent Pages)	DATE
	U	"ECR Plasma Etching of Chemically Vapor Deposited Thin Films"; Pearson et al.; Electronics Letters; (1992); 28(9); pp. 822-824	

* A copy of this reference is not being furnished with this Office action.
See Manual of Patent Examining Procedure, Section 707.05(a).